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PATENT



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

INVENTOR: C. Obszarny)

EXAMINER: P. Kim

SERIAL NO.: 09/116,395 ✓)

ART UNIT: 2851

FILING DATE: 16 July 1998 ✓)

DATE: 19 June 2000

#121B
gmm
6-24-00

FOR: **APPARATUS AND METHOD FOR IN-SITU ADJUSTMENT OF
LIGHT TRANSMISSION IN A PHOTOLITHOGRAPHY
PROCESS**

AMENDMENT

Assistant Commissioner of Patents
Washington, DC 20231

RECEIVED
JUN 23 2000
TECHNOLOGY CENTER 2800

Dear Sir:

Responsive to the Office Action mailed 20 March 2000, please amend the application
as follows:

In the Claims

Please amend claims 1, 3, 7, 17 and 18 as follows:

1. (twice amended) An apparatus for varying optical transmission intensity on a substrate
wafer in a photolithography process comprising:

a first polarizer capable of adjustment during optical transmission such that an optical
image focused on said substrate wafer is varied in contrast, said adjustment made
relative to a second polarizer; and,

a photo mask patterned with a plurality of optically transparent and optically opaque
regions, wherein said transparent regions are impregnated with said second
polarizer[,] fixed in a predetermined direction, and said opaque regions comprise a

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